



## Future Normal in Semiconductor

2025-02-14(금), 10:55-12:40

좌장: 추후업데이트 예정

### D. Thin Film Process Technology 분과

### [FC2-D] Atomic Layer Deposition - II

<p>초청 FC2-D-1 10:55-11:25</p>	<p><b>Challenges and Advancements in ALD of Chalcogenide Materials for Next-Generation Microelectronics</b> Taeyong Eom Department of Semiconductor System Engineering, Sejong University</p>
<p>FC2-D-2 11:25-11:40</p>	<p><b>Atomic Layer Deposition of Ge-Sb-Se Ternary Alloy for 3D Vertical Selector-Only Memory</b> Jeongwoo Seo<sup>1</sup>, Minu Cho<sup>1</sup>, Inkyu Sohn<sup>1</sup>, Youngjae Kang<sup>2</sup>, Jong-bong Park<sup>2</sup>, Kiyeon Yang<sup>2</sup>, Wooyoung Yang<sup>2</sup>, and Hyungjun Kim<sup>1</sup> <sup>1</sup>School of Electrical and Electronic Engineering, Yonsei University, <sup>2</sup>Device Research Center, SAIT</p>
<p>FC2-D-3 11:40-11:55</p>	<p><b>Unraveling the Influence of Substrate Surface and Temperature on Microstructural Evolution of Crystalline MoS<sub>2</sub> in Atomic Layer Deposition</b> Seung Ho Ryu<sup>1,2</sup> and Seong Keun Kim<sup>1,2</sup> <sup>1</sup>KU-KIST Graduate School of Converging Science and Technology, Korea University, <sup>2</sup>Electronic Materials Research Center, Korea Institute of Science and Technology</p>
<p>FC2-D-4 11:55-12:10</p>	<p><b>Atomic Layer Deposition of Low Work Function Metallic Films via Composition Control Using Discrete Feeding ALD</b> Ji Won Han<sup>1</sup>, Kyun Seong Dae<sup>2</sup>, Yoon Jeong Kim<sup>1</sup>, Ji Sun Heo<sup>1</sup>, Woo-Hee Kim<sup>1</sup>, Ji-Hoon Ahn<sup>1</sup>, Jae Hyuck Jang<sup>2</sup>, Deok-Yong Cho<sup>3,4</sup>, and Tae Joo Park<sup>1</sup> <sup>1</sup>Department of Materials Science and Chemical Engineering, Hanyang University, <sup>2</sup>Center for Research Equipment, KBSI, <sup>3</sup>Institute of Photonics, Electronics and Information Technology, Jeonbuk National University, <sup>4</sup>Department of Physics, Jeonbuk National University</p>
<p>FC2-D-5 12:10-12:25</p>	<p><b>Atomic Layer Deposition for Molybdenum Interconnects</b> Hyun Jin Lim<sup>1</sup>, Sang-Kuk Han<sup>1</sup>, Hyo Jin Ahn<sup>1</sup>, Young Seo Na<sup>2</sup>, Yeh Been Im<sup>1</sup>, Won Jae Choi<sup>2</sup>, and Changhwan Choi<sup>1,2</sup> <sup>1</sup>Division of Materials Science and Engineering, Hanyang University, <sup>2</sup>Department of Semiconductor Engineering, Hanyang University</p>



# 제 32회 한국반도체학술대회

The 32nd Korean Conference on Semiconductors

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## *Future Normal in Semiconductor*

FC2-D-6 12:25-12:40	Growth of Metallic Ru Thin Film by Oxidant-free Atomic Layer Deposition below 100 °C 민경민, 이한보람 Department of Materials Science and Engineering, Incheon National University
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